

Solar control glazing

1. Field of the invention

The field of the invention is that of solar-control glazings consisting of a glass substrate bearing a system of thin layers, at least one thin layer of which gives said solar-control properties. This functional layer is
5 combined with dielectric layers whose role is especially to regulate the reflection, transmission and hue properties and the protection against mechanical or chemical impairment of the properties of the glazing.

More precisely, the invention relates to glazings intended to be fitted in buildings, but also in motor vehicles. Depending on these uses, certain
10 required properties may differ as explained later.

Solar-control glazings have a plurality of functionalities. They especially concern the prevention of heating in the passenger compartment of a motor vehicle, in particular with respect to sunlight passing through a transparent sunroof, or with respect to a building exposed to sunlight when this sunlight is
15 sufficiently intense. According to certain embodiments, this prevention of heating may be obtained while maintaining appropriate light transmission.

Glazings, especially for motor vehicles, must also participate toward establishing temperature regulation conditions in winter by avoiding energy loss out of the passenger compartment or of the building. The glazings
20 must thus have low-emission properties. They counter the emission of energy radiation from the passenger compartment or the building.

In the case of glazings for buildings, they are furthermore required to be capable of withstanding heat treatments without their color, especially in reflection, being substantially modified. The object is to be able to place side by
25 side heat-treated glazings and others that have not been, without color differences appearing.

In the rest of the description, the optical properties are defined for glazings whose substrate is made of ordinary clear "float" glass 4 mm thick. The choice of the substrate obviously has an influence on these properties. For ordinary clear glass, the light transmission through 4 mm, in the absence of a
5 layer, is approximately 90% with 8% reflection, measured with a source conforming to the D65 "daylight" illuminant normalized by the CIE and at a solid angle of 2°. The energy measurements are taken according to standard EN 410.

The term "glass" is understood to denote an inorganic glass. This means a glass with a thickness at least greater than or equal to 0.5 mm and less
10 than or equal to 20.0 mm, preferentially at least greater than or equal to 1.5 mm and less than or equal to 10.0 mm, comprising silicon as one of the essential constituents of the vitreous material. For certain applications, the thickness may be, for example, 1.5 or 1.6 mm, or 2 or 2.1 mm. For other applications, it will be, for example, about 4 or 6 mm. Clear or extra-clear, or bulk-colored or surface-
15 colored silico-sodio-calcic glasses are preferred.

The presence of the layer systems may pose color problems. Constructors usually demand that glazings offer, both in transmission and in reflection, a coloring that is as neutral as possible and thus of gray appearance. Slightly green or blueish colorings are also possible. The layer systems, and in
20 particular the nature, indices and thicknesses of the dielectric layers surrounding the functional layers, are chosen especially to control these colorings.

Motor vehicle glazings may in theory be multiple to give the vehicle better insulating properties, especially heat insulation. In reality, such implementations are exceptional. The vast majority of these glazings consist of
25 single glazings, which are either monolithic or laminated. In these two cases, in order for the low-emission nature to be suitably expressed, the layer system is necessarily on a face that is not sheltered from mechanical or chemical stresses. The systems in question must thus have very good resistance to these possible attacking factors.

In practice, to limit the risks of impairment, the layer systems are especially on the face of the glazing oriented toward the passenger compartment. However, even in this position, they must afford very good mechanical strength.

The layer systems according to the invention must also lend
5 themselves to the fashioning of glazings. Those used in vehicles are especially the subject of heat treatments during fashioning, especially the bending of glass sheets, or during toughening intended especially to give the glass sheets reinforced mechanical properties. The layers used according to the invention must withstand these treatments without their properties being degraded. Treatments of
10 this type demand temperatures which exceed 600°C for about 10 minutes. The layers must conserve their qualities when subjected to these temperatures.

In many applications requiring the availability of glazings with high light transmission, the choice of the functional layers demands that they be particularly transparent. The most common is to select one or more metallic layers
15 of very low thickness: for example, one or more silver layers arranged between dielectric layers which protect them and both minimize the reflection and adjust the neutrality. The layer systems obtained in the assembly are limited by having a certain level of fragility, especially mechanical fragility, even in the presence of special protective layers.

20 For glazings that do not require high light transmission, and even optionally for which the transmission must remain low, the choice of the layer systems affords wider diversity.

The prior art proposes glazings comprising sunlight-absorbing metallic or metal alloy layers, of nitrides or oxynitrides of various metals and
25 especially of NiCr, Mo, W, Ta, CoCr, Al, Nb or Zr. To enable these metallic layers to have good resistance, especially good mechanical strength, it is also proposed to provide dielectric layers known to be relatively hard. In this field, the most common layers are those of silica, SiO₂, and of silicon nitride, Si₃N₄.

The prior proposals at least partly satisfy the requirements for the envisaged use of the glazings according to the invention. There nevertheless remain needs for improvement, especially as regards the resistance to heat treatments.

5 An objective of the invention is in particular to overcome these disadvantages of the prior art.

More precisely, one object of the invention, in at least one of its embodiments, is to provide a glazing equipped with a layer system which is capable of undergoing a heat treatment at high temperature, of toughening and/or
10 bending type, preferably without significant modification of its hue in substrate-side and/or layer-side transmission and/or reflection, such that a glazing that has not been heat-treated can be juxtaposed with its heat-treated version without an observer being able to detect a significant difference in the overall esthetic appearance.

15 Another object of the invention, in at least one of its embodiments, is to provide a glazing equipped with a layer system which has good thermal, chemical and mechanical stability.

An object of the invention is also, in at least one of its embodiments, to provide a glazing whose layer system can be placed in an outer
20 position without necessarily having to be protected from the external environment by another substrate.

4. Summary of the invention

The invention relates to a solar-control glazing comprising on at least one of the faces of a glass substrate a layer system comprising at least one
25 sunlight-absorbing layer and dielectric layers surrounding said sunlight-absorbing layer, characterized in that the sunlight-absorbing layer is a metallic layer based on tungsten alloyed with at least nickel, the layer system comprising, between the

substrate and the sunlight-absorbing layer, at least one layer made of a dielectric material based on a compound selected from silicon oxide, aluminum oxide, silicon nitride, aluminum nitride, mixed aluminum-silicon nitrides, silicon oxynitride and aluminum oxynitride, and, over the sunlight-absorbing layer, at
5 least one layer made of a dielectric material based on a compound selected from silicon oxide, aluminum oxide, silicon nitride, aluminum nitride, mixed aluminum-silicon nitrides, silicon oxynitride and aluminum oxynitride.

The general principle of the invention is based on the presence of a sunlight-absorbing metallic layer which is based on tungsten alloyed with at least
10 nickel, said layer being set between at least two layers based on at least one dielectric material selected from silicon oxide, aluminum oxide, mixed aluminum-silicon oxides, silicon nitride, aluminum nitride, mixed aluminum-silicon nitrides, silicon oxynitride, aluminum oxynitride and mixed aluminum-silicon oxynitrides. The inventors have determined that, surprisingly, such a layer system has good
15 chemical, thermal and mechanical durability. Specifically, the sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel, set between at least two layers based on at least one dielectric material, brings about a decrease in solar energy transmission, said layer conserving its absorption properties more particularly after a heat treatment.

20 In the present description, the term "based on tungsten" refers to a layer comprising at least 30% by weight of tungsten, preferably at least 35% and advantageously at least 37% or at least 40%. The proportion of nickel in the sunlight-absorbing metallic layer is at least 9% by weight, preferably at least 20% by weight and advantageously at least 25% by weight, for example 30%, 35% or
25 40% by weight.

For the sunlight-absorbing layer, the term "metallic layer" means a layer having essentially metallic nature. However, it is not excluded for this layer optionally to contain a few traces of nitrogen or oxygen. Specifically, the atmosphere during the deposition of this metallic layer may consist of pure noble

gas, for example 100% argon, or the atmosphere may contain a small amount of nitrogen or oxygen originating from neighboring deposition zones. In the case where the dielectric layers which surround the absorbing layer are silicon nitrides, the metallic target intended to form the absorbing layer may even be arranged in
5 the same deposition chamber, without distinct isolation with the silicon nitride deposition zones, since the nitrogen will be predominantly attracted by the silicon. In this case, the surrounding atmosphere may contain a relatively high percentage of nitrogen and thus, even if the nitrogen predominantly combines with silicon, the absorbing metallic layer may contain a small amount of nitrogen, without
10 thereby losing its metallic nature. In the case where the dielectric layers which surround the absorbing layer are oxides or oxynitrides, there may also be a small amount of oxygen therein originating from the neighboring deposition zones in the deposition atmosphere.

The term "layer based on a dielectric material" also means layers
15 doped with at least one other element, containing up to a maximum of about 10% by weight of this other element, these layers having dielectric properties that do not differ in practice from the layers consisting of said dielectric material. Thus, for example, when the layer is made of silicon nitride or oxide, it may contain up to 10% by weight of aluminum (for example layers deposited by the cathodic
20 sputtering process using a silicon target containing up to 10% by weight of aluminum). The dielectric layers according to the invention may also consist of several individual layers comprising or essentially consisting of these same materials. The dielectric layers may also be deposited via the well-known technique known as PECVD (plasma-enhanced chemical vapor deposition).

25 Thus, the invention is founded on an entirely novel and inventive approach based on the selection of a sunlight-absorbing metallic layer which is based on tungsten alloyed with at least nickel.

Advantageously, the glazing according to the invention is such that the sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel also comprises an additional metal selected from Ti, Nb, Zr, Ta and Cr.

The inventors have determined, surprisingly, that the addition of a
5 metallic compound selected from Ti, Nb, Zr, Ta and Cr to the alloy based on tungsten alloyed with nickel makes it possible to obtain layer systems whose thermal and chemical resistance and mechanical strength are improved.

According to a preferred embodiment of the preceding mode, the
glazing according to the invention is such that the metallic layer based on tungsten
10 alloyed with at least nickel comprises chromium. The inventors have determined, surprisingly, that the addition of Cr to the alloy based on tungsten alloyed with nickel makes it possible to obtain layer systems whose thermal and chemical resistance and mechanical strength are most particularly improved.

According to a preferred embodiment, the glazing according to the
15 invention is such that the sunlight-absorbing metallic layer comprises from 50% to 90% by weight of tungsten, and nickel and chromium in a nickel/chromium weight ratio of between 100/0 and 50/50, preferentially 80/20.

The inventors have determined, surprisingly, that the selection of
such an alloy makes it possible to obtain layer systems whose thermal and
20 chemical resistance and mechanical strength are most particularly improved. The inventors have also determined, surprisingly, that the metallic layer based on tungsten alloyed with at least nickel has the sunlight-absorbing properties most particularly required for its use in layer systems for motor vehicle or building glazings.

25 According to a preferred embodiment, the glazing according to the invention is such that the metallic layer based on tungsten alloyed with at least nickel has a geometrical thickness of at least 2 nm, preferentially of at least 3 nm

and of not more than 30 nm, preferentially of at least 3 nm and of not more than 25 nm.

The inventors have determined, surprisingly, that the metallic layer based on tungsten alloyed with at least nickel, which has such thicknesses, has
5 infrared absorption properties that are most particularly required for its use in layer systems for motor vehicle or building glazing or as a glazed element of a household electrical appliance, such as an oven door.

Preferably, the metallic layer based on tungsten alloyed with at least nickel has a geometrical thickness of at least 5 nm and preferably of at least
10 6 nm.

According to an advantageous embodiment, the glazing according to the invention is such that the layer of dielectric material between the substrate and the sunlight-absorbing layer based on tungsten alloyed with at least nickel has an optical thickness of at least 2 nm and of not more than 200 nm, advantageously
15 of at least 10 nm and of not more than 200 nm, preferentially of at least 40 nm and of not more than 180 nm.

The optical thickness of a layer of dielectric material is obtained by multiplying the geometrical (physical) thickness of the layer under consideration by the refractive index of the material constituting it.

20 According to a preferred embodiment, the glazing according to the invention is such that the layer of dielectric material located over the sunlight-absorbing layer based on tungsten alloyed with at least nickel has an optical thickness of at least 20 nm and of not more than 200 nm.

According to a first preferred embodiment, the sunlight-absorbing
25 metallic layer is the base functional layer of the layer system. The advantage of this layer system is that it is extremely simple and very resistant.

Preferably, the layer system comprises at least two sunlight-absorbing layers. This characteristic makes it possible more easily to adapt optical and thermal properties of the layer system as desired. Advantageously, these two sunlight-absorbing layers are separated by a dielectric layer, for example made of silicon nitride. A particularly suitable structure is the following:

substrate/Si₃N₄/NiCrW/Si₃N₄/NiCrW/ Si₃N₄.

According to a second preferred embodiment, the glazing according to the invention is such that the layer system comprises at least one additional silver-based metallic layer such that the or each silver-based layer is surrounded by a dielectric coating. This dielectric coating may be formed from a material as described above in relation with the other embodiments of the invention. It may also be any dielectric material that is well known in the field, for instance zinc stannate or ZnO, which may or may not be doped.

In this second embodiment, the base functional layer of the layer system is the silver-based layer which reflects infrared radiation, thus allowing greater solar-control efficacy while at the same time conserving higher light transmission and thus a significant gain in selectivity. The addition of an additional silver-based layer is surprising since this type of layer generally shows poor resistance to high-temperature heat treatment and moreover embrittles the layer system assembly from the mechanical and chemical viewpoint. In general, the presence of a silver layer prevents the positioning of the layer system in contact with the outer environment and requires the protection of the layer system using an additional substrate. The inventors have discovered, surprisingly, that the invention makes it possible to overcome these drawbacks.

The combination of a silver-based layer with the sunlight-absorbing layer makes it possible, firstly, simultaneously to obtain infrared radiation-reflecting properties, afforded by the silver-based layer, combined with sunlight-absorbing properties.

According to a first preferred form of this second embodiment, at least one of the dielectric coatings comprises at least two dielectric layers and the sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel is inserted between these two dielectric layers of this dielectric coating. The
5 inventors have found that this configuration effectively separates the infrared-reflecting function from the sunlight-absorbing function, which makes it possible more easily to optimize the two functions, in particular when it is desired to improve the crystallographic quality of the silver to obtain lower emissivity, for example using a layer based on ZnO under the silver, which is often referred to as
10 a wetting layer, and/or over the silver, without loss of absorption function of the sunlight-absorbing metallic layer. Furthermore, this arrangement better protects the sunlight-absorbing metallic layer during the heat treatment so that it integrally conserves its absorption function as much as possible.

Preferably, the first dielectric layer of the first dielectric coating,
15 deposited on the glass substrate and in contact therewith, is a layer of mixed zinc-tin oxide, advantageously containing at least 20% tin, even more preferentially a layer of mixed zinc-tin oxide in which the zinc-tin proportion is close to 50-50% by weight (Zn_2SnO_4). This arrangement is advantageous for the resistance to high-temperature heat treatment. The mixed zinc-tin oxide forms an excellent barrier to
20 the alkali metal ions migrating from the glass substrate at the high temperature of the heat treatment, especially the toughening treatment. It has and also conserves good adhesion to the glass substrate. It also has a good level of deposition when compared, for example, with SiO_2 or Al_2O_3 , and it shows good durability when compared, for example, with pure ZnO or bismuth oxide. It may also be
25 advantageous in that it has less of a tendency to generate a fog after a heat treatment of the stack, when compared, for example, with Ti or Zr oxides. The layer consisting of an oxide, in direct contact with the substrate, advantageously has a thickness of at least 5 nm, preferably of at least 8 nm and more preferentially of at least 10 nm. These minimum thickness values make it
30 possible, inter alia, to ensure the chemical durability of the product that has not been heat-treated, but also to ensure the resistance to the heat treatment.

Preferably, the two said dielectric layers sandwiching the sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel are based on silicon nitride or aluminum nitride. This ensures very good protection of the sunlight-absorbing metallic layer during the high-temperature heat treatment.

5 Preferred but in no way limiting examples of this embodiment may be represented schematically as follows:

G/Si₃N₄/NiCrW/Si₃N₄/D/ZnO/Ag/AZO/Si₃N₄/ZnO/Ag/AZO/Si₃N₄/NiCrW/Si₃N₄;

G/D/ZnO/Ag/AZO/D/ZnO/Ag/AZO/D/Si₃N₄/NiCrW/Si₃N₄;

G/Si₃N₄/NiCrW/Si₃N₄/D/ZnO/Ag/AZO/D/ZnO/Ag/AZO/D/Si₃N₄;

10 G/Si₃N₄/NiCrW/Si₃N₄/D/ZnO/Ag/B/D/ZnO/Ag/B/D/TiN (or TiO₂);

G/Si₃N₄/NiCrW/Si₃N₄/D/ZnO/Ag/AZO/D/Si₃N₄/D/ZnO/Ag/AZO/D/Si₃N₄;

G/D/ZnO/Ag/AZO/D/Si₃N₄/NiCrW/Si₃N₄/D/ZnO/Ag/AZO/D/Si₃N₄;

G/D/ZnO/Ag/B/D/Si₃N₄/NiCrW/Si₃N₄/D/ZnO/Ag/B/D/Si₃N₄;

G representing the substrate, preferably a sheet of ordinary sodio-calcic glass; B representing a layer acting as a barrier to the oxidation of the silver, which is well known in the field; AZO representing a barrier layer based on zinc oxide, preferably doped with aluminum, deposited from a ceramic (cathode) target of zinc oxide (preferably doped with aluminum) sputtered in an atmosphere based on argon with little or no oxygen; D representing one or more dielectric layers, especially based on zinc stannate, doped or undoped ZnO, or another material known in the field and which is suitable for this type of layer stacking, for example TiO₂, ZrO₂ or a mixture thereof, or a nitride such as AlN. As a variant, AZO may be replaced with other barriers that are well known in the field and suited to the desired properties for the formed layer system, for instance a Ti oxide, which is undoped or doped with niobium or zirconium, preferably obtained from a ceramic target formed from the oxide to be deposited, or pure ZnO. The

15
20
25

examples given above use NiCrW as sunlight-absorbing layer as concrete examples, but NiCrW may also be replaced with another material based on tungsten alloyed with nickel, such as WNi or WNiV, in pure metallic form or with traces of nitrogen or oxygen.

5 Preferably, according to this first form of the second embodiment of the invention, the layer system comprises, at least once, the following succession of layers: "silicon or aluminum nitride or a mixture thereof/sunlight-absorbing layer/silicon or aluminum nitride or a mixture thereof/intercalating transparent oxide/wetting layer based on zinc oxide/additional silver-based
10 metallic layer". It has been found that the use of a wetting layer based on ZnO with insertion of an intercalating transparent oxide layer between the nitride layer protecting the sunlight-absorbing layer and the wetting layer makes it possible to greatly reduce, or to prevent, the formation of marks that are unacceptable in the visual appearance of the coated substrate that has undergone a high-temperature
15 heat treatment, which have a tendency to be formed during the heat treatment in the absence of this specific succession of layers. It has also been found that, without this intercalating transparent oxide layer, the surface electrical resistance, and thus also the emissivity, have a tendency to increase undesirably following the heat treatment, whereas, by virtue of the presence of this intercalating oxide
20 layer, the emissivity is at least conserved, or even beneficially reduced, following the heat treatment. The intercalating transparent oxide layer may be an oxide based on ZnO, SnO₂, TiO₂, ZrO₂ or a mixture thereof, while being different from the wetting layer. Preferably, the intercalating transparent oxide layer is a mixed zinc-tin oxide containing at least 20% tin and at least 10% zinc.

25 According to a second preferred form of this second embodiment, the additional silver-based metallic layer is located in the stack directly over and/or under the sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel.

The inventors have determined, surprisingly, that the presence of the sunlight-absorbing layer makes it possible to reduce the risks of chemical deterioration of the silver-based layer when said silver-based layer is in direct contact with the sunlight-absorbing layer based on tungsten alloyed with at least
5 nickel.

Preferably, according to this second form of the second embodiment, the glazing according to the invention is such that the silver-based metallic layer(s), if there are several of them, have a thickness of at least 9 nm, preferentially of at least 13 nm and of not more than 23 nm, more preferentially of
10 at least 15 nm and of not more than 22 nm.

According to this embodiment, the sunlight-absorbing metallic layer preferably has a geometrical thickness of between 0.5 and 8 nm and advantageously between 0.5 and 5 nm.

According to this embodiment, this sunlight-absorbing layer may
15 be placed either under the additional silver-based layer or over the silver-based layer. Preferably, it is placed on either side of the additional silver-based metallic layer, each layer preferably having a thickness within the range indicated above, i.e. preferably between 0.5 and 5 nm. It has been found that this is the best
17 arrangement for spreading the sunlight absorption on either side of the infrared-
20 reflecting layer.

According to a first preferred implementation of the first embodiment, the glazing according to the invention is such that it comprises on at least one of the faces of a glass substrate a layer system successively comprising at least:

- 25
- A layer made of a dielectric material based on at least one chemical compound selected from the group consisting of silicon oxide, aluminum oxide, mixed aluminum-silicon oxides, silicon nitride, aluminum nitride, mixed aluminum-

- 5 silicon nitrides, silicon oxynitride, aluminum oxynitride and mixed aluminum-silicon oxynitrides, preferentially from silicon nitride, aluminum nitride and mixed aluminum-silicon nitrides, the layer of dielectric material having an optical thickness of at least 10 nm and of not more than 200 nm, preferentially of at least 40 nm and of not more than 180 nm,
- 10 • A sunlight-absorbing metallic layer, said metallic layer comprising from 30% to 90%, preferably from 40% to 90% and advantageously from 50% to 90% by weight of tungsten, and nickel and chromium in a nickel/chromium weight ratio of between 100/0 and 50/50, preferentially 80/20, the metallic layer based on tungsten alloyed with at least nickel having a geometrical thickness of at least 2 nm, preferentially of at least 3 nm, and of not more than 30 nm, preferentially of at least 3 nm and of not more than 25 nm,
- 15 • A layer made of a dielectric material based on at least one chemical compound selected from the group consisting of silicon oxide, aluminum oxide, mixed aluminum-silicon oxides, silicon nitride, aluminum nitride, mixed aluminum-silicon nitrides, silicon oxynitride, aluminum oxynitride and mixed aluminum-silicon oxynitrides, preferentially from silicon nitride, aluminum nitride and mixed aluminum-silicon nitrides, the layer of dielectric material having an optical thickness of at least 20 nm and of not more than 200 nm.
- 20
- 25

According to a second preferred implementation of the first embodiment, the glazing according to the invention is such that it comprises on at

least one of the faces of a glass substrate a layer system successively comprising at least:

- 5 • A layer made of a dielectric material based on at least one chemical compound selected from the group consisting of silicon oxide, silicon nitride and silicon oxynitride, the layer of dielectric material having an optical thickness of at least 10 nm and of not more than 200 nm, preferentially of at least 40 nm and of not more than 180 nm,
- 10 • A sunlight-absorbing metallic layer, said metallic layer comprising from 30% to 90%, preferably from 40% to 90% and advantageously from 50% to 90% by weight of tungsten, and nickel and chromium in a nickel/chromium weight ratio of between 100/0 and 50/50, preferentially 80/20, the metallic layer based on tungsten alloyed with at least nickel having a geometrical thickness of at least 2 nm, preferentially of at least 3 nm, and of not more than 30 nm, preferentially of at least 3 nm and of not more than 25 nm,
- 15 • A layer made of a dielectric material with an optical thickness of at least 20 nm and of not more than 400 nm, preferably between 20 and 200 nm, based on at least one chemical compound selected from the group consisting of silicon nitride and silicon oxynitride.
- 20

According to a preferred implementation of the first form of the second embodiment, the layer system comprises n additional silver-based metallic layers, with $n \geq 1$, each additional silver-based metallic layer being surrounded by layers of dielectric material, and comprises at least once the following succession of layers: "silicon or aluminum nitride or a mixture thereof/sunlight-absorbing layer/silicon or aluminum nitride or a mixture thereof/intercalating transparent oxide/wetting layer based on zinc oxide/additional silver-based metallic layer", in

which the additional silver-based metallic layer has a geometrical thickness of at least 8 nm and the sunlight-absorbing layer has a geometrical thickness of between 0.5 and 8 nm. It may be a layer system having two or three, or even four, silver-based metallic layers, a sunlight-absorbing layer, surrounded by its specific dielectric layers, preferably being placed between the first and the second silver-based layer starting from the substrate. It has been discovered that this particular succession of layers makes it possible to greatly reduce, or to prevent, the formation of colored marks that are observed after heat treatment when this sequence is not respected, and in particular when the intercalating transparent oxide layer is not present between the nitride layer that protects the sunlight-absorbing layer and the wetting layer based on ZnO. It has also been found that, by virtue of the presence of this intercalating oxide layer, the surface electrical resistance, and thus also the emissivity, are at least conserved, or even beneficially reduced, following the heat treatment, instead of increasing undesirably during the heat treatment.

According to a preferred implementation of the second form of the second embodiment, the glazing according to the invention is such that it comprises on at least one of the faces of a glass substrate a layer system successively comprising at least:

- A layer made of a dielectric material based on at least one chemical compound selected from the group consisting of silicon and/or aluminum nitride or oxynitride, the layer of dielectric material having an optical thickness of at least 10 nm and of not more than 200 nm, preferentially of at least 40 nm and of not more than 180 nm,
- A sunlight-absorbing metallic layer, said metallic layer comprising from 30% to 90%, preferably from 40% to 90% and advantageously from 50% to 90% by weight of tungsten, and nickel and chromium in a nickel/chromium

- weight ratio of between 100/0 and 50/50, preferentially 80/20, the metallic layer based on tungsten alloyed with at least nickel having a geometrical thickness of at least 0.5 nm, preferentially of at least 1 nm, and of not more than 8 nm, preferentially of at least 1 nm and of not more than 5 nm,
- An additional silver-based metallic layer having a geometrical thickness of at least 9 nm, preferentially of at least 13 nm, and of not more than 22 nm,
 - A second sunlight-absorbing metallic layer, said metallic layer comprising from 30% to 90%, preferably from 40% to 90% and advantageously from 50% to 90% by weight of tungsten, and nickel and chromium in a nickel/chromium weight ratio of between 100/0 and 50/50, preferentially 80/20, the metallic layer based on tungsten alloyed with at least nickel having a geometrical thickness of at least 0.5 nm, preferentially of at least 1 nm, and of not more than 8 nm, preferentially of at least 1 nm and of not more than 5 nm,
 - A layer of a dielectric material based on silicon nitride or oxynitride having an optical thickness of at least 20 nm and of not more than 400 nm, preferably between 20 and 200 nm.

According to the four preceding implementations, other additional layers may be added, either directly to the substrate, or as an outer protective layer, or inside the stack of the layer system, so as to give the base layer system additional properties and/or protection, for instance additional outer protection against mechanical or chemical attacking factors, a barrier against alkalis originating from the substrate, different optical properties, an improvement in the

electrical properties of the metallic layers, an improvement in the level of deposition, or any additional function. The additional layers must, however, preferably be chosen so that they do not disrupt the ability of the layer system to undergo a high-temperature heat treatment. In particular, care will advantageously
5 be taken to ensure that these additional layers do not undergo substantial modifications, especially structural modifications, during the heat treatment, to prevent them from resulting in modifications in the optical properties of the layer system during the heat treatment.

The heat treatments, especially of bending/toughening type, may
10 also induce more or less sensitive modifications in the optical properties and especially in the hues. Preferentially, these variations should be minimized such that, whether or not they are heat-treated, the glazings have a virtually unchanged appearance.

Conventionally, measurement of the colorimetric variations is
15 performed from the coordinates of the CIELAB system. The colorimetric variation is expressed by the expression noted ΔE^* , which expression corresponds to the formula:

$$\Delta E^* = (\Delta L^{*2} + \Delta a^{*2} + \Delta b^{*2})^{1/2}$$

in which ΔL^* represents the difference between the colorimetric
20 coordinates L^* of the glazing before and after heat treatment,

Δa^* represents the difference between the colorimetric coordinates
 a^* of the glazing before and after heat treatment,

Δb^* represents the difference between the colorimetric coordinates
 b^* of the glazing before and after heat treatment.

25 More particularly, the glazing according to the invention has a colorimetric variation in transmission, ΔE^*_{tr} :

$$\Delta E^*_{tr} = (\Delta L^*_{tr}{}^2 + \Delta a^*_{tr}{}^2 + \Delta b^*_{tr}{}^2)^{1/2}$$

of less than 8, preferentially less than 5, more preferentially less than 3, when said glazing is subjected to a temperature of at least 630°C and of not more than 670°C for 7 minutes.

- 5 The glazing according to the invention has, optionally in addition, a colorimetric variation in glass-side reflection, ΔE^*_{rg} :

$$\Delta E^*_{rg} = (\Delta L^*_{rg}{}^2 + \Delta a^*_{rg}{}^2 + \Delta b^*_{rg}{}^2)^{1/2}$$

of less than 8, preferentially less than 5, more preferentially less than 3, when said glazing is subjected to a temperature of at least 630°C and of not more than 670°C
10 for 7 minutes.

The glazing according to the invention has, optionally in addition to the two preceding properties, a colorimetric variation in layer-side reflection, ΔE^*_{rl} :

$$\Delta E^*_{rl} = (\Delta L^*_{rl}{}^2 + \Delta a^*_{rl}{}^2 + \Delta b^*_{rl}{}^2)^{1/2}$$

- 15 of less than 8, preferentially less than 5, more preferentially less than 3, when said glazing is subjected to a temperature of at least 630°C and of not more than 670°C for 7 minutes.

- According to a particular embodiment, the glazing according to the invention is such that the thickness of the sunlight-absorbing metallic layer is
20 chosen so that the light transmission for a substrate consisting of clear glass 4 mm thick is at least equal to 2% and not more than 75%. In the case of the use as a motor vehicle sunroof, the light transmission will preferably be between 2% and 10%, preferably between 6% and 8%. In the case of application in a building, the light transmission will preferably be between 10% and 70%, preferably between
25 10% and 60%, advantageously between 10% and 50% and favorably between

20% and 40%. Specifically, the sunlight-absorbing metallic layer governs the light and energy transmissions, and, as such, the thicker it is, the more it absorbs.

According to a particular embodiment, the glazing according to the invention is such that the optical thickness of the dielectric layers is chosen so that
5 the layer-side reflection is at least 1% and not more than 40%. The dielectric layers, in particular the upper layer, especially governs the reflection of the system. In a known manner, the alternation of layers with high and low refractive indices makes it possible to control the reflection. The thickness of the layers is also a determining factor. Within the limit of the thicknesses indicated previously,
10 increasing the thickness of the layer of dielectric material located over the sunlight-absorbing metallic layer reduces the intensity of the layer-side reflection.

As a variant, when low light reflection is desired, especially layer-side reflection, two or even more functional layers formed from sunlight-absorbing metallic layers are preferably arranged with a dielectric layer between
15 these two layers, according to the following structure, for example: dielectric layer as described in the main claim/sunlight-absorbing layer/dielectric layer as described in the main claim/sunlight-absorbing layer/dielectric layer as described in the main claim. The desired total thickness for the sunlight absorption is subdivided into two, or even into as many absorbing layers used. As an
20 illustration, here is a preferred concrete structure: $\text{Si}_3\text{N}_4/\text{NiCrW}/\text{Si}_3\text{N}_4/\text{NiCrW}/\text{Si}_3\text{N}_4$. This structure facilitates the production of very low layer-side light reflection, for example only 2%.

According to a preferred embodiment of the invention, the substrate-side measured light reflection is at least 27%, preferably at least 30%
25 and advantageously at least 35%. This characteristic makes it possible to obtain a pleasant esthetic effect that is highly appreciated on the commercial market in certain regions, especially by virtue of the shiny appearance of the face of the glazing.

The layer system of the glazing according to the invention makes it possible to obtain this esthetic effect more easily, especially by appropriately adjusting the optical thickness of the dielectric layers so as to control correctly the optical interference effect. One appropriate means consists in limiting the optical

5 thickness of the first dielectric layer, placed between the substrate and the sunlight-absorbing layer, to a low value. However, this solution has a limit since the thickness of this first dielectric layer must be sufficient to allow high-temperature heat treatment of the layer system without deterioration of its properties, especially on account of the migration of elements originating from the

10 substrate. Another preferred means consists in giving the second dielectric layer, placed over the sunlight-absorbing layer, a high optical thickness that is within a specific range. Preferably, the second dielectric layer, placed over the sunlight-absorbing layer, has an optical thickness (geometrical thickness multiplied by the refractive index of the material) of between 70 and 170 nm, preferably between 80

15 and 140 nm and advantageously between 110 and 130 nm.

Preferably, the light reflection measured on the substrate side is at least 2 times, advantageously at least 2.5 times and preferentially at least 3 times greater than the light reflection measured on the layer-system side. Preferably, the light reflection measured on the substrate side is at least 15% and advantageously

20 at least 20% greater than the light reflection measured on the layer-system side. Given that, in order to obtain the best solar-control effect, the layer is placed in position 2 (starting from the exterior), this characteristic makes it possible to obtain an exterior reflection (measured on the substrate side) allowing the production of the desired pleasant esthetic effect while at the same time avoiding

25 the mirror effect when looking through the glazing from the interior of the space closed by the glazing, thus improving the light transmission and the visibility through the glazing. This combination of high exterior reflection, to obtain a desired esthetic effect, with low interior reflection is an essential characteristic of this embodiment of the invention. The mirror effect viewed from the interior,

30 which prevents correct vision through the glazing from the chamber closed by the

glazing, is thus avoided. A high thickness of the second dielectric layer is a fundamental condition.

According to an advantageous embodiment for obtaining this difference in light reflection between the substrate side and the layer-system side,
5 the layer of dielectric material placed over the sunlight-absorbing layer is multilayered and comprises a material with a high refractive index, of greater than 2. In the context of the present invention, this dielectric with a high refractive index is a material that withstands the heat treatment without significant structural modification. A specific example of such a material is titanium oxide, for example
10 doped with zirconium or niobium, especially a mixture of titanium oxide and zirconium oxide in a proportion of 40% to 60% each. Another example of such a material is zirconium oxide. Preferably, this high-index material is placed between the sunlight-absorbing layer and the outermost dielectric layer of the layer system.

Preferably, the layer system ends with a thin protective layer based
15 on a mixed titanium-zirconium oxide.

Glazings according to the invention find various applications by adapting their properties via adjustment of the layers and especially of their thicknesses.

The glazings according to the invention may form part of double
20 glazings and, in this case, the layer system may be placed in the space between the two sheets of glass, which limits the risks of impairment, especially mechanical impairment. Nevertheless, two of the significant features of the layer systems proposed for the glazings according to the invention are their mechanical strength and their chemical resistance. In the embodiments without an additional silver-
25 based metallic layer or with an additional silver-based metallic layer but without oxide in the layer system, this resistance or strength is such that they may be used with the layer system exposed without any other protection. In the latter case, the glazing may equally be composed of a single sheet of glass, the layer systems being applied onto one face of this sheet. It may also be a laminated glazing

comprising two or more sheets of glass, the sheets being connected by means of intercalating sheets of thermoplastic material according to the conventional techniques in this field.

5 In these applications on a single glazing, the layer system is not protected from the environment. Even in the case of laminated glazing, the layers may be on an outer face so that they can play their role in controlling energy transmission by acting on the emissivity of the surface.

10 When the favored functionality is the low-emissive nature of the glazing, the layer system is preferably arranged on the face oriented toward the interior of the vehicle or building. This position leads to the greatest reflection of the long-wavelength infrared rays to keep the heat inside the passenger compartment or the building. For vehicles, this position corresponds to the layer on the face oriented toward the passenger compartment. In this position, the layer system resists all the better when the stresses, especially for fixed glazings
15 (sunroof, rear window, etc.), are relatively limited.

The glazing according to the invention thus finds its application as a glazed element of a motor vehicle: sunroof, windshield, side window, rear window (the layer system preferably being on the face exposed to the passenger compartment) and a glazing element of buildings.

20 More particularly, the glazing according to the invention finds its application as a motor vehicle sunroof.

Specifically, motor vehicle constructors are in search of a solution that avoids placing a curtain (veil) in the roof for protecting against sunlight. The absence of this curtain leads to a saving in weight (~6 kg) and thus to a reduction
25 in fuel consumption, resulting in less expelled CO₂. Without any curtain, the thermal comfort must, despite everything, be ensured for the passengers, i.e. no overheating in summer and no cold wall sensation in winter. In an electric vehicle, there is no heat coming from the thermal engine that can be used to heat the

passenger compartment of the vehicle and the body heat must absolutely be maintained inside (no loss through the sunroof).

The glazing according to the invention also finds its application as a glazed element of a household electrical appliance such as an oven door, where
5 it may also provide a desired esthetic effect. It shows good resistance to the various chemical and/or mechanical attacking factors due to this particular type of application.

As already indicated above several times, the glazing according to the invention obviously also finds its application as a glazed element of a
10 building. In this application case, the glazing may form a double or triple glazing with the layer system arranged facing the closed space inside the multiple glazing. The glazing may also form a laminated glazing whose layer system may be in contact with the thermoplastic adhesive material connecting the substrates, in general PVB. The glazing according to the invention is, however, particularly
15 useful when the layer system is facing the outer environment, whether it is a single glazing or a laminated glazing, but also optionally a multiple glazing.

Needless to say, the glass substrate may be a bulk-tinted glass, such as a gray, blue or green glass, to absorb sunlight in addition, or to form a private space with low light transmission so as to dissimulate the passenger compartment
20 of the vehicle, or an office in a building, from external regard.

As a variant of the various embodiments including an additional silver-based metallic layer, the invention also includes the introduction not only of a single silver-based metallic layer but also of two, or even three, or even four, silver-based metallic layers. In this case, the sunlight-absorbing metallic layer(s)
25 may be arranged in immediate proximity (on either side or on one side or the other) to several, or to each, silver-based layer. Preferably, the sunlight-absorbing metallic layers will be arranged on either side of the first silver-based metallic layer starting from the substrate. Dielectric layers based on silicon and/or aluminum nitride or oxynitride are preferably arranged between each silver-based

metallic layer according to a repetition of the examples with a single functional layer.

5. Description of preferred embodiments of the invention

5 Examples of glazings according to the invention, but also comparative examples ("R"), are given in table I below. The optical properties are defined, as single glass, for glazings whose substrate is made of ordinary clear "float" glass 4 mm thick. The layers are in order, from left to right, starting from the glass. The approximate thicknesses are expressed in nm.

10 Tables I and Ia: Examples of glazings according to the invention and comparative examples of the performance of glazings according to the invention with prior art glazings, the coatings being deposited on clear glass 4 mm thick. The light transmissions (TL) and the layer-side light reflections (Rl) and glass-side light reflections (Rg) are also indicated (in %) for certain examples.

Table I:

Ex.	Coating	TL	RI	Rg	ΔE^*_{Tl}	ΔE^*_{RI}	ΔE^*_{Rg}
1R	SiN (40nm)/NiCr (1nm)/Ag (18nm)/NiCr (1nm)/SiN (56nm)				3.9	5.1	1.7
2R	SiN (20nm)/NiCr (8.5nm)/SiN (35nm)	39	11	17	1.70	4.33	3.84
3R	SiN (20nm)/NiCr (13.7nm)/SiN (35nm)	27	15	25	2.61	6.92	2.32
4R	SiN (20nm)/NiCr (22nm)/SiN (35nm)	14	22	36	3.56	3.55	1.74
5R	SiN (87nm)/NiCr (13.7nm)/SiN (30nm)	28	22	17	1.95	6.59	4.60
1	SiN (40nm)/NiCrW (1nm)/Ag (18nm)/NiCrW (1nm)/SiN (56nm)				2.1	2.7	0.5
2	SiN (20nm)/NiCrW (8.5nm)/SiN (35nm)	30	18	24	0.90	3.44	0.30
3	SiN (20nm)/NiCrW (13.7nm)/SiN (35nm)	19	25	33	1.02	1.68	0.84
4	SiN (20nm)/NiCrW (22nm)/SiN (35nm)	10	31	41	1.13	2.50	0.20
5	SiN (87nm)/NiCrW (13.7nm)/SiN (30nm)	20	30	24	0.41	2.94	1.47
6	SiN (53nm)/NiCrW (16.5nm)/SiO _x (85.2nm)	21	28	22	-2.5	2.9	2
7	SiN (65nm)/NiCrW (25nm)/SiO _x (80.4nm)	10	33	30	2.3	2.1	1.3
8	SiN (10nm)/NiCrW (7.5nm)/SiO _x (73nm)	37	9	22	0.8	2.4	0.4
9	SiN (10nm)/NiCrW (21nm)/SiO _x (73nm)	11	30	42	1	1.6	0.4
10	SiN (10nm)/NiCrW (13nm)/SiO _x (90nm)	21	18	33	1.3	2.6	0.4

Ex.	Coating	TL	RI	Rg	ΔE^*_{TL}	ΔE^*_{RI}	ΔE^*_{Rg}
11	SiO _x (20nm)/NiCrW (11.7nm)/SiN (29nm)				-	-	-
12	SiO _x (20nm)/NiCrW (6.9nm)/SiN (29nm)				-	-	-
13	SiO _x (20nm)/NiCrW (20nm)/SiN (29nm)				-	-	-
14	SiN (35.5nm)/NiCrW (0.5nm)/Ag (17.4nm)/NiCrW (0.5nm)/SiN (53.5nm)				-	-	-
15	SiN (36.1nm)/NiCrW (0.5nm)/Ag (17.4nm)/NiCrW (0.5nm)/SiN (53.5nm)				-	-	-
16	SiN (79.7nm)/NiCrW (2.8nm)/Ag (17.9nm)/NiCrW (0.7nm)/SiN (45.1nm)				-	-	-
17	SiN (37.3nm)/NiCrW (1.4nm)/Ag (21.3nm)/NiCrW (1.4nm)/SiN (38.7nm)				-	-	-
18	SiN (59.4nm)/NiCrW (3.4nm)/Ag (19.5nm)/NiCrW (3.4nm)/SiN (49.3nm)				-	-	-
19	SiN (13.5nm)/NiCrW (10.6nm)/SiN (60nm)/NiCrW (7.3nm)/SiN (60nm)				1.6	3.4	1.6

Table Ia:

Ex.	Coating (thickness in nm)					TL	RI	Rg	ΔE^*_{Ti}	ΔE^*_{RI}	ΔE^*_{Rg}
	SiN	NiCrW	SiN	NiCrW	SiN						
34	28.5	7.8	27.4	0.0	0.0	33.3	24.1	17.4	0.8	1.1	1.2
35	22.9	7.9	23.9	0.0	0.0	31.1	25.4	17.6	0.7	0.9	1.1
36	10.0	4.3	34.0	2.0	26.5	38.4	9.0	25.0	0.7	1.7	1.3
37	26.0	11.0	46.0	0.0	0.0	32.6	7.4	31.0	0.5	7.3	0.6
38	54.1	4.4	64.5	7.0	44.8	22.5	5.2	6.6	1.1	2.5	2.6
39	22.9	7.9	23.9	0.0	0.0	31.1	25.4	17.6	0.7	0.9	1.1
40	72.1	4.0	50.9	6.5	20.0	20.9	16.2	8.3	1.1	0.6	0.6
41	54.5	2.9	89.4	9.6	34.2	21.2	19.8	12.0	1.2	2.0	2.3
42	95.0	5.7	70.7	4.5	19.0	20.9	21.9	13.5	0.7	2.3	2.2
43	100.0	1.8	28.7	5.1	51.0	38.6	3.4	26.5	0.7	0.9	3.9
44	100.0	1.8	28.7	5.1	47.0	38.5	3.6	25.5	0.7	1.0	3.7
45	129.1	5.2	52.0	0.0	0.0	45.8	4.9	30.0	0.9	1.2	3.8
46	140.0	6.8	39.0	0.0	0.0	37.4	10.3	26.3	1.0	2.6	3.6
47	138.0	6.8	39.0	0.0	0.0	37.4	10.1	26.0	1.0	2.2	3.6
48	39.0	1.0	79.3	6.0	118.7	29.0	28.0	13.9	1.4	2.6	1.8
49	17.7	4.4	60.0	4.9	25.0	24.6	14.1	9.8	0.6	0.1	0.6
50	78.3	3.0	69.4	5.8	62.6	30.9	4.7	10.8	1.8	7.8	4.6
51	15.0	6.1	55.0	5.5	33.7	19.2	8.8	13.2	0.6	0.4	0.3
52	15.0	6.1	57.5	5.5	33.7	19.0	9.0	12.6	0.7	0.5	0.3
53	14.6	4.7	62.1	3.1	95.0	27.6	16.7	12.1	0.4	1.2	2.5
54	14.6	4.7	62.1	3.1	92.5	28.2	15.9	11.8	0.4	1.3	2.4
55	9.5	5.7	61.3	3.3	100.0	23.9	15.4	15.7	0.4	2.2	2.3
56	90.0	12.0	12.0	0.0	0.0	19.0	42.3	17.4	1.3	0.8	3.8
57	24.2	19.9	25.0	0.0	0.0	47.0	39.8	37.3	3.6	4.2	3.4

The sunlight-absorbing metallic layers, the additional silver-based metallic layers and the dielectric layers are applied via a cathodic sputtering technique under usual conditions for this type of technique. As a variant, the dielectric layers are applied via the well-known technique known as PECVD (plasma-enhanced chemical vapor deposition).

The silicon nitride dielectric layers are produced from metal targets in an atmosphere consisting of a mixture of argon (30-70%) and nitrogen (70-30%) at a total pressure of 4 mTorr (0.53 Pa). The nickel-chromium (80/20 nickel/chromium)-tungsten (50% by weight of NiCr and 50% of W in the NiCrW

alloy) layers are deposited from metal cathodes in an atmosphere of argon alone. As a variant, the deposition atmosphere of this NiCrW metal alloy comprises a small amount of nitrogen or oxygen originating from the neighboring deposition zones. As a result, the formed NiCrW layer, while conserving its essentially
5 metallic nature, contains a small amount of nitrogen or oxygen. The properties obtained are similar. The silicon oxide dielectric layers are produced starting with a silicon-based target in an atmosphere containing argon and oxygen.

The layer-side or substrate-side light transmission TL and light reflection are measured on the samples with the illuminant D65, 2°. The CIE
10 colorimetric coordinates L*, a* and b* are also measured before and after heat treatment with the illuminant D65, 10°. The angle at which the measurements are taken is 8°.

The samples are subjected to a heat treatment comprising maintenance at 670°C for 7 minutes 30 seconds. The transmission and reflection
15 variations in ΔE^* are also given in the tables. In the examples, the notations SiN denote the silicon nitrides without representing a chemical formula, it being understood that the products obtained are not necessarily rigorously stoichiometric, but are those obtained under the indicated deposition conditions and which are in the region of the stoichiometric products. The notations SiO_x
20 denote the silicon oxides without representing a chemical formula, it being understood that the products obtained are not necessarily rigorously stoichiometric, but are those obtained under the indicated deposition conditions and which are in the region of the stoichiometric products. The SiN or SiO_x layers may contain up to a maximum of about 10% by weight of aluminum originating
25 from the target. The dielectric layer according to the invention may furthermore consist of a plurality of individual layers comprising or essentially consisting of the above materials.

The mechanical strengths and chemical resistances of the glazings according to the invention without a silver layer are characterized by successfully

passing the tests defined in standard EN1096-2 for class B coatings. In addition, the glazings according to the invention also satisfy the requirements of the following tests:

- 5 ▪ the salt spray test (NSS: *Neutral Salt Spray*) according to standard ISO 9227-2006, preferably for at least 10 days;
- the air-conditioned chamber test according to standard EN1036-2008, preferably for at least 10 days; and
- the Cleveland test according to standard ISO 6270-1:1998, preferably for at least 10 days;
- 10 ▪ the acid resistance test (SO₂) according to standard EN 1096-2;
- the AWRT test (*Automatic wet rub test*) described below: A piston covered with a cotton cloth is brought into contact with the layer to be evaluated and moved back and forth over its surface. The piston bears a weight so as to apply a force of 33 N to a finger having a diameter of 17
15 mm. The rubbing of the cotton over the coated surface damages (removes) the layer after a certain number of cycles. The test is used to define the limit at which the layer discolours (partial removal of the layer) and scratches appear therein. The test is carried out for 10, 50, 100, 250, 500
20 and 1000 cycles in various separate locations on the sample. The sample is observed under an artificial sky in order to determine whether discoloring or scratching is visible on the sample. The AWRT result indicates the number of cycles resulting in no or very little degradation (invisible to the naked eye under a uniform artificial sky at a distance of 80 cm from the sample);
- 25 ▪ the dry brush test (DBT) according to standard ASTM D2486-00 (test method "A"), preferably for at least 1000 cycles,

this being measured before and after optional heat treatment.

Table II: The examples that follow were performed with other proportions of NiCr and of W in the sunlight-absorbing metal alloy. As for the preceding examples, the example numbers bearing the letter ("R") are comparative examples, and the numbers without this letter are examples according to the invention. The results (OK for good; KO for unacceptable; and S for satisfactory) for three chemical resistance tests are also indicated: air-conditioned chamber (CC), Cleveland test (Clev) and salt spray (SS).

The same structure below was used: 25 nm SiN/functional layer/55 nm SiN (SiN means Si_3N_4 , optionally doped with aluminum to make the starting silicon target conductive). The various layers are deposited in the same manner as in the preceding examples. The constitution of the functional layer is given in table II below. The NiCr percentages relative to W are given on a weight basis. The light transmission of these examples is about 7% and the sun factor is about 20%.

Ex.	Functional layer	ΔE^*_{TI}	ΔE^*_{RI}	ΔE^*_{Rg}	CC	Clev	SS
6R	41 nm pure W	1.2	4.8	1.1	KO	S	S
7R	35 nm pure NiCr	3.9	33.8	7.2	OK	OK	OK
20	28 nm NiCrW (63/37%)	1.4	5.6	0.4	OK	OK	OK
21	28.4 nm NiCrW (43/57%)	1.0	5.8	0.4	OK	OK	OK
22	30.3 nm NiCrW (33/67%)	1.4	4.8	0.6	OK	OK	S
23	34 nm NiCrW (22/78%)	1.4	4.4	0.8	S	S	S
24	36.1 nm NiCrW (12/88%)	2	3.8	1.2	S	S	S

Table III: The example of a layer system, deposited on a glass substrate, reproduced in table III below presents a structure with two functional layers each formed from a sunlight-absorbing metallic layer forming a glazing according to the invention. The notation conventions are the same as for table II.

Ex.	Coating	ΔE^*_{TI}	ΔE^*_{RI}	ΔE^*_{Rg}	CC	Clev	SS
25	15 nm SiN / 10.6 nm	1.6	3.4	1.6	OK	OK	OK

	NiCrW (63/37%) / 60 nm						
	SiN / 7.3 nm NiCrW						
	(43/57%) / 60 nm SiN						

The variation in the thicknesses of the dielectric layers, within reasonable limits, does not significantly affect the modification of the hue during the heat treatment, or the durability, but, of course, it does modify the starting esthetic appearance (and in particular the hue).

5 **Table IV:** Examples 26-33 of a layer system, deposited on a glass substrate, reproduced in table IV below relate more particularly to the embodiment of the invention in which the light reflection on the substrate side is high, and in particular higher than the light reflection on the layer-system side. The sunlight-absorbing metallic layer is an alloy comprising 50% nickel-
10 chromium (80-20%) and 50% tungsten. The notation conventions are the same as for table I. The figures in parentheses are the physical thicknesses in nm for the various layers. The properties (in % for the light transmission and reflection) are given in monolithic glazing after heat treatment. The name "TZO" represents a mixed oxide comprising 50% TiO₂ and 50% ZrO₂.

15

Ex.	Coating	TL	RI	Rg	ΔE^*_{TI}	ΔE^*_{RI}	ΔE^*_{Rg}
26	SiN (15)/NiCrW (9.8)/SiN (50.6)	32.5	6	34.6	0.6	6	1
27	SiN (15)/NiCrW (15.4)/SiN (48.2)	21.6	11.5	40.1	0.9	5.3	0.7
28	SiN (15)/NiCrW (24.5)/SiN (48)	10.5	17.5	45	2.1	3.7	1.5
29	SiN (78.4)/NiCrW (18)/SiN (49.5)	20.4	14.9	30.9	1.2	4.9	0.7
30	SiN (15)/NiCrW (10.1)/TZO (29.7)/SiN (20)	32.4	6.1	39.2	1.2	3.1	0.9
31	SiN (15)/NiCrW (16.2)/TZO (27.2)/SiN (20)	21.1	9.2	45.1	0.9	2.6	0.9
32	SiN (15)/NiCrW (25)/TZO (13.2)/SiN (34.7)	10.8	14.9	47.7	0.4	2.8	0.6
33	SiN (75.4)/NiCrW (18.9)/TZO (23.7)/SiN (23.6)	21.3	11.9	33.5	1.4	1.4	0.3

Table Va below gives examples with two additional silver-based metallic layers, the sunlight-absorbing layer being in the first dielectric coating arranged between the substrate and the first silver-based layer. The various layers are deposited under the same conditions as for the examples of table I. The properties are measured in the same manner and are given in table Vb. The examples of table Va also underwent a heat treatment identical to that described for the examples of table I and the variations in the properties are, in the same manner, given in ΔE^* , either in transmission ΔE^*_{TI} (or ΔE^*_{tr}), or in layer-side reflection (ΔE^*_{RI}), or in glass substrate-side reflection (ΔE^*_{Rg}). Furthermore, the coordinates L^* , a^* , b^* and Y (which represents either the total light transmission or the total light reflection) are also indicated as transmission (TL), as glass substrate-side reflection (Rg) and as layer-system-side reflection (RI), and also the variation in total light transmission (Δ_{TL}), and the variation in glass substrate-side (Δ_{Rg}) and layer-system-side (Δ_{RI}) total reflection. The name ZSO5 represents a

mixed zinc-tin oxide formed from a cathode of a zinc-tin alloy containing 52% by weight of zinc and 48% by weight of tin to form the spinel structure of zinc stannate Zn_2SnO_4 . The term "AZO" refers to a zinc oxide doped with aluminum, obtained by cathode sputtering, from a ceramic cathode formed by the oxide to be deposited, under a neutral or slightly oxidizing atmosphere. As a variant, AZO
5 may be replaced with other barriers that are well known in the field and suited to the desired properties for the formed layer system, for instance a Ti oxide, which is undoped or doped with niobium or zirconium, preferably obtained from a ceramic target formed from the oxide to be deposited, or pure ZnO. B represents a
10 layer acting as a barrier to the oxidation of silver, which is well known in the field. D represents one or more dielectric layers, especially based on zinc stannate, doped or undoped ZnO, or another material known in the field, which is suited to this type of layer stacking, for example a nitride such as AlN. M represents the wetting layer based on ZnO, which is undoped or doped with aluminum. IR
15 represents the functional layers that reflect infrared radiation. ABS represents the sunlight-absorbing layer.

The examples given in table VIa are, in the same manner, examples with two additional silver-based metallic layers as for table Va, but this time the sunlight-absorbing layer is in the second dielectric coating arranged between the
20 first silver-based layer and the second silver-based layer. The properties obtained are given in table VIb in the same manner as for table Vb. The name TZO_{65} means a mixed titanium-zirconium oxide with 35% zirconium and 65% titanium, different from TZO (50/50).

Table VIIa below gives examples with three additional silver-based
25 metallic layers, the sunlight-absorbing layer being in the first dielectric coating arranged between the substrate and the first silver-based layer. The corresponding properties are given in table VIIb, as single glass, for a clear glass substrate 6 mm thick, not heat-treated. The sun factor value (g) is also indicated.

Table VIIIa below also gives examples with three additional silver-based metallic layers, but this time the sunlight-absorbing layer is in the second dielectric coating arranged between the first silver-based layer and the second silver-based layer. The corresponding properties are given in table VIIIb, as single
5 glass, for a clear glass substrate 6 mm thick, not heat-treated. The sun factor value (g) is also indicated.

Needless to say, the invention is not limited to the implementation examples mentioned.

Table Va:

Ex.	D1a	ABS	D1b		M	IR1	B	D2			M	IR2	B	D3		
	SiN	NiCrW	SiN	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	TZO
58	10	1.1	10	8	5	10.5	5	15.35	35	15.35	5	14.7	5	11.7	20	3
59	10	1.8	10	10.4	5	11.4	5	14.2	35	14.2	5	14.9	5	11.6	20	3
60	10	2.7	10	12.8	5	12.6	5	14.05	35	14.05	5	14.8	5	11.9	20	3

Table Vb:

Ex.	Δ_{TL}	Δ_{RI}	Δ_{Rg}	ΔE^*_{TL}	ΔE^*_{RI}	ΔE^*_{Rg}	TL				Rg				RI			
							Y	L*	a*	b*	Y	L*	a*	b*	Y	L*	a*	b*
58	-1.2	0.4	0.6	2.3	3.1	6.2	68.9	86.4	-3.3	2.6	6.8	31.7	0.5	-11.8	4.3	24.8	-3.5	-5.6
59	1.2	0.4	-0.1	1.3	1.5	1.3	61.2	82.5	-4.4	2.9	5.8	29.1	0	-9.3	4.4	25	3	-2.1
60	2.2	0.6	-0.5	1.3	5.3	2.1	50.5	76.5	-4.4	-1.1	6.4	30.6	0.6	-7.6	7.9	33.7	-0.4	6.3

Table VIa:

Ex.	D1	M	IR1	B	D2a		ABS	D2b		M	IR2	B	D3		P	
	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	NiCrW	SiN	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	TZO	
61	36.6	5	10	5	29.7	10	0.8	35	6.1	5	15.2	5	10.1	20	3	
62	38.9	5	13.4	5	5.5	35	1.1	10	33	5	14.9	5	9.5	20	3	
63	38.9	5	15.5	5	9.6	20	1.7	25	29.6	5	15.6	5	9.5	20	3	
	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	NiCrW	SiN	TZO ₆₅	ZnO	Ag	AZO	ZSO5	SiN	TZO	
64	38	4.0	14.1	5.5	24.1	20	1.1	25	10	4	15.5	5.5	9.9	21	3	
	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	NiCrW	SiN	ZSO5	TZO ₆₅	ZnO	Ag	AZO	ZSO5	SiN	TZO
65	42	4	14.1	5.5	24.8	20	1.1	25	9.2	3	4	15.5	5.5	8.3	21	3

Table VIb:

Ex.	Δ_{TL}	Δ_{RI}	Δ_{Rg}	ΔE^*_{TL}	ΔE^*_{RI}	ΔE^*_{Rg}	TL				Rg				RI			
							Y	L*	a*	b*	Y	L*	a*	b*	Y	L*	a*	b*
61	2.1	2.1	0.7	1.1	5.3	2.5	66.9	85.4	-4.5	4.0	5.9	29.4	-0.3	-8.5	6.0	29.4	6.7	-4.6
62	1.9	1.6	0.1	1.5	4.9	1.7	57.2	80.3	-5.0	3.4	11.4	40.2	-1.1	-4.9	5.2	27.8	2.0	-17.5
63	1.7	2.0	-0.7	2.8	6.7	2.8	43.3	71.8	-6.8	2.9	18.0	49.6	0.9	-4.6	5.4	28.6	11.4	-24.3
64	-0.7	2.0	-0.1	2.0	5.2	2.2	57.3	80.4	-4.7	2.2	12.1	41.3	-0.5	-0.4	4.9	26.9	-0.4	-15.9
65	2.8	1.6	-0.8	1.6	4.7	2.0	57.0	80.2	-4.6	3.3	11.4	40.3	-2.6	-4.3	5.3	27.9	0.3	-13.8

Table VIIa:

Ex.	D1a	ABS	D1b		M	IR1	B	D2			M	IR2	B	D3			M	IR3	B	D4	
	SiN	NiCrW	SiN	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	ZSO5	ZnO	Ag	AZO	ZSO5	SiN
66	16.2	1.8	13.4	1.1	5	11.5	4	20	20	21.1	5	15.2	4	15	17	29.1	5	16.2	4	14	18
67	16.2	1.8	13.4	1.1	5	11.5	4	61.1	0	0	5	15.2	4	32	0	29.1	5	16.2	4	14	18

Table VIIb:

Ex.	g	ΔE^*_{TL}	ΔE^*_{RI}	ΔE^*_{Rg}	TL				Rg				RI			
					Y	L*	a*	b*	Y	L*	a*	b*	Y	L*	a*	b*
66	37	3	4	8	36.5	80	-6	-0.8	6.7	31.1	-3.9	-0.9	2.9	19.6	12.8	-9
67	37	3	4	8	36.5	80	-6	-0.8	6.7	31.1	-3.9	-0.9	2.9	19.6	12.8	-9

Table VIIIa:

Ex.	D1	M	IR1	B	D2a		ABS	D2b		M	IR2	B	D3			M	IR3	B	D4	
	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	NiCrW	SiN	ZSO5	ZnO	Ag	AZO	ZSO5	SiN	ZSO5	ZnO	Ag	AZO	ZSO5	SiN
68	17.7	5	9.2	4	19	20	0.8	15	10	5	15.1	4	20	20	25.8	5	15.5	4	14	18.9

Table VIIIb:

Ex.	g	ΔE^*_{TL}	ΔE^*_{RI}	ΔE^*_{Rg}	TL				Rg				RI			
					Y	L*	a*	b*	Y	L*	a*	b*	Y	L*	a*	b*
68	37.5	1.5	7.1	3.5	57	80.3	-5.9	-1.5	5.1	27.1	1.6	-5.8	4.1	24.8	5.4	-13.5

CLAIMS

1. A solar-control glazing comprising on at least one of the faces of a glass substrate a layer system comprising at least one sunlight-absorbing layer and dielectric layers surrounding said sunlight-absorbing layer, characterized in that the sunlight-absorbing layer is a metallic layer based on tungsten alloyed with
5 at least nickel, the layer system comprising, between the substrate and the sunlight-absorbing layer, at least one layer made of a dielectric material based on a compound selected from silicon oxide, aluminum oxide, silicon nitride, aluminum nitride, mixed aluminum-silicon nitrides, silicon oxynitride and aluminum oxynitride, and, over the sunlight-absorbing layer, at least one layer
10 made of a dielectric material based on a compound selected from silicon oxide, aluminum oxide, silicon nitride, aluminum nitride, mixed aluminum-silicon nitrides, silicon oxynitride and aluminum oxynitride.

2. The glazing as claimed in claim 1, such that the sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel also
15 comprises at least one additional metal selected from Ti, Nb, Zr, Ta and Cr.

3. The glazing as claimed in claim 2, such that the sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel comprises Cr.

4. The glazing as claimed in any one of the preceding claims, such that the sunlight-absorbing metallic layer comprises from 50% to 90% by
20 weight of tungsten, and nickel and chromium in a nickel/chromium weight ratio of between 100/0 and 50/50, preferentially 80/20.

5. The glazing as claimed in any one of the preceding claims, such that the sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel has a geometrical thickness of at least 2 nm, preferentially of at least 3
25 nm and of not more than 30 nm, preferentially of at least 3 nm and of not more than 25 nm.

6. The glazing as claimed in claim 5, such that the metallic layer based on tungsten alloyed with at least nickel has a geometrical thickness of at least 5 nm and preferably of at least 6 nm.

7. The glazing as claimed in any one of the preceding claims,
5 such that the layer of dielectric material between the substrate and the sunlight-absorbing layer based on tungsten alloyed with at least nickel has an optical thickness of at least 10 nm and of not more than 200 nm, preferentially of at least 40 nm and of not more than 180 nm.

8. The glazing as claimed in any one of the preceding claims,
10 such that the layer of dielectric material located over the sunlight-absorbing layer based on tungsten alloyed with at least nickel has an optical thickness of at least 20 nm and of not more than 200 nm.

9. The glazing as claimed in any one of the preceding claims, such that the layer system comprises at least two sunlight-absorbing layers.

10. The glazing as claimed in any one of the preceding claims,
15 such that the layer system comprises at least one additional silver-based metallic layer such that the or each silver-based layer is surrounded by a dielectric coating.

11. The glazing as claimed in claim 10, such that at least one of the dielectric coatings comprises at least two dielectric layers and the sunlight-
20 absorbing metallic layer based on tungsten alloyed with at least nickel is inserted between these two dielectric layers of this dielectric coating.

12. The glazing as claimed in claim 11, such that the two said dielectric layers sandwiching the sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel are based on silicon nitride or aluminum
25 nitride.

13. The glazing as claimed in claim 10, such that the additional silver-based metallic layer is located in the stack directly over and/or under the

sunlight-absorbing metallic layer based on tungsten alloyed with at least nickel.

14. The glazing as claimed in any one of claims 10 to 13, such that the additional silver-based metallic layer(s) have a thickness of at least 9 nm, preferentially of at least 13 nm and of not more than 23 nm, more preferentially of
5 at least 15 nm and of not more than 22 nm.

15. The glazing as claimed in any one of claims 10 to 14, such that the sunlight-absorbing metallic layer has a geometrical thickness of between 0.5 and 8 nm and preferably between 0.5 and 5 nm.

16. The glazing as claimed in any one of the preceding claims, in
10 which the colorimetric variation in transmission, ΔE^*_{TL} , is less than 8, preferentially less than 5, more preferentially less than 3, when said glazing is subjected to a temperature of at least 630°C and of not more than 670°C for 7 minutes.

17. The glazing as claimed in any one of the preceding claims, in
15 which the colorimetric variation in glass-side reflection, ΔE^*_{RG} , is less than 8, preferentially less than 5, more preferentially less than 3, when said glazing is subjected to a temperature of at least 630°C and of not more than 670°C for 7 minutes.

18. The glazing as claimed in any one of the preceding claims, in
20 which the colorimetric variation in layer-side reflection, ΔE^*_{RL} , is less than 8, preferentially less than 5, more preferentially less than 3, when said glazing is subjected to a temperature of at least 630°C and of not more than 670°C for 7 minutes.

19. The glazing as claimed in any one of the preceding claims, in
25 which the thickness of the sunlight-absorbing metallic layer is chosen so that the light transmission for a substrate consisting of clear glass 4 mm thick is at least equal to 2% and not more than 75%.

20. The glazing as claimed in any one of the preceding claims, in which the optical thickness of the dielectric layers is chosen so that the layer-side reflection is at least 1% and not more than 40%.

21. The glazing as claimed in any one of the preceding claims,
5 characterized in that the substrate-side measured light reflection is at least 27%, preferably at least 30% and advantageously at least 35%.

22. The glazing as claimed in any one of the preceding claims, characterized in that the light reflection measured on the substrate side is at least 2 times, preferably at least 2.5 times and advantageously at least 3 times greater
10 than the light reflection measured on the layer-system side.

23. The glazing as claimed in claim 12, characterized in that the layer system comprises the following succession: layer of silicon nitride or of aluminum nitride/sunlight-absorbing layer/layer of silicon nitride or of aluminum nitride/layer of intercalating transparent oxide based on Zn, Sn, Ti or Zr oxide, or
15 a mixture thereof, different from the wetting layer/wetting layer based on zinc oxide/additional silver-based metallic layer.

24. The glazing as claimed in claim 23, characterized in that the sunlight-absorbing metallic layer has a geometrical thickness of between 0.5 and 8 nm and preferably between 0.5 and 5 nm.

20 25. The glazing as claimed in either of claims 23 and 24, characterized in that the intercalating transparent oxide is a mixed zinc-tin oxide or a mixed titanium-zirconium oxide, preferably a mixed zinc-tin oxide containing at least 20% tin and 10% zinc.

25 26. The use of a solar-control glazing as claimed in any one of the preceding claims, as a glazed element of a motor vehicle, as a glazing element of buildings or as a glazed element of a household electrical appliance such as an oven door.